Application No.: 10/528,125

Filing Date: November 21, 2005

AMENDMENTS TO THE CLAIMS

 (Currently amended) A method for electrolytic coating of a material with an aluminum, magnesium or alloys of aluminum and magnesium, said method comprising

pre-treating immersing an aluminum/magnesium alloy or zinc/magnesium alloy material by immersing in an electrolytic bath consisting of an electrolyte for pretreatment and a halogen-free, aprotic solvent, wherein said material is electrically connected as an anode therein, and anodically charging the material, and

performing the electrolytic coating in the same electrolytic bath immediately thereafter by reversing polarity of the material, thereby performing the electrolytic coating in the same electrolytic immediately thereafter, the electrolytic bath consisting of organoaluminum compounds of general formulas (I) and (II)

$$M[(R^1)_3AI-(H-AI(R^2)_2)_n-R^3]$$
 (I)

$$Al(R^4)_3$$
 (II)

as the electrolyte, wherein n is equal to 0 or 1, M is sodium or potassium, and R^1 , R^2 , R^3 , R^4 are the same or different, R^3 , R^2 , R^3 , R^4 -being a C_1 - C_4 alkyl groups, and the [[a]] halogen-free, aprotic solvent being used as solvent for the electrolyte, wherein impurities introduced into the electrolytic bath during the pretreatment step do not impede the deposition of magnesium, aluminum or alloys of aluminum and magnesium on the material during the electrolytic coating step.

- (Previously presented) The method according to claim 1, wherein a mixture of the complexes K[AlEt₄], Na[AlEt₄] and AlEt₃ is employed as the electrolyte.
- 3. (Previously presented) The method according to claim 2, wherein a molar ratio of said complexes K[AlEta]. Na[AlEta] to AlEta is from 1:0.5 to 1:3.
- (Previously presented) The method according to claim 2, wherein 0 to 25 mole-% Na[AlEt₄] is employed, relative to the mixture of the complexes K[AlEt₄] and Na[AlEt₄].
- (Currently amended) The method according to Claim 2, wherein a mixture of 0.8 mol K[AlEt₄], 0.2 mol Na[AlEt₄], 2.0 mol AlEt₃ in 3.3 mol toluene is used as the <u>electrolytic</u> electrolyte bath.
- 6. (Previously presented) The method according to claim 1, wherein a mixture of $Na[Et_3Al-H-AlEt_3]$ and $Na[AlEt_4]$ and $AlEt_3$ is used as the electrolyte.

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(Previously presented) The method according to claim 6, wherein a molar ratio
of Na[Et₃Al-H-AlEt₃] to Na[AlEt₄] is from 4:1 to 1:1.

- (Previously presented) The method according to claim 7, wherein a molar ratio of Na[AlEt₄] to AlEt₇ is 1:2.
- 9. (Currently amended) The method according to Claim 8, wherein a mixture of 1 mol Na[Et₃Al-H-AlEt₃], 0.5 mol Na[AlEt₄] and 1 mol AlEt₃ in 3 mol toluene is used as the electrolytic electrolyte bath.
- (Previously presented) The method according to Claim 1 wherein the electrolytic coating is performed at temperatures of from 80 to 105°C.
- (Currently amended) The method according to Claim 1 wherein the <u>pre-treating</u> step <u>pre-treatment</u> is performed for a period of from 1 to 20 minutes.
- (Currently amended) The method according to Claim 1, wherein the <u>pre-treating step pretreatment</u> is performed at an anodic load of the material with a current density of from 0.2 to 2 A/dm²?
- 13. (Previously presented) The method of Claim 3, wherein the molar ratio of said complexes K[AlEt₄], Na[AlEt₄] to AlEt₃ is 1:2.
- (Previously presented) The method according to claim 4 wherein 5 to 20 mole-% Na[AlEt₄] is employed, relative to the mixture of the complexes K[AlEt₄] and Na[AlEt₄].
- 15. (Previously presented) The method of Claim 7, wherein the molar ratio of Na[Et₃Al-H-AlEt₃] to Na[AlEt₄] is 2:1.
- (Previously presented) The method of Claim 10, wherein the electrolytic coating is performed at temperatures of from 91 to 100°C.
- 17. (Currently amended) The method of Claim 11, wherein the <u>pre-treating step</u> pretreatment is performed for a period of from 5 to 15 minutes.
- 18. (Currently amended) The method of Claim 12, wherein the pre-treating step pretreatment is performed at an anodic load of the material with a current density of from 0.5 to 1.5 A/dm².